Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1098	(438/514).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	OFF	2005/08/03 09:38
L2	140	(position$3 or align$4 or locat$4 or diplace$4 or adjust$4) and impurity and mask and l1	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/03 08:46
L3	118	(position$3 or align$4 or locat$4 or diplace$4 or adjust$4) and impurity and mask and l1 and @ad<"20030108"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/03 08:47
L4	15	semiconductor adj substrate same insulat$4 near3 (film or layer or region) and ((impurity or doping) near3 (region or film or layer)) and ((position$4 or locat$4 or adjust$4 or displace$4 or align$4) adj mark).clm.	US-PGPUB	OR	ON	2005/08/03 09:46